FASH 62B Course Outline as of Fall 2014

CATALOG INFORMATION

Dept and Nbr: FASH 62B   Title: FLAT PATTERN DESIGN 2
Full Title: Flat Pattern Design 2
Last Reviewed: 9/20/2010

Units			Course Hours per Week		Nbr of Weeks	Course Hours Total	
Maximum	2.00		Lecture Scheduled	1.50	17.5	Lecture Scheduled	26.25
Minimum	2.00		Lab Scheduled	1.50	6	Lab Scheduled	26.25
			Contact DHR	0		Contact DHR	0
			Contact Total	3.00		Contact Total	52.50
			Non-contact DHR	0		Non-contact DHR	0

Total Out of Class Hours: 52.50   Total Student Learning Hours: 105.00

Title 5 Category: AA Degree Applicable
Grading: Grade or P/NP
Repeatability: 00 - Two Repeats if Grade was D, F, NC, or NP
Also Listed As:
Formerly: CLTX 50B

Catalog Description:
Further studies in patternmaking techniques, with an emphasis on professional skills, unique styling details, and more complex design components. In addition to women's wear, patterns for jackets, coats, and active wear for men's and children's wear are discussed. Development of specialized slopers (such as jackets, etc.) included.

Prerequisites/Corequisites:
Course Completion of FASH 62A (or CLTX 50A or CLTX 5A or CLTX 5 or CLTX 175)

Recommended Preparation:
Previous or concurrent enrollment in FASH 60 (formerly CLTX 60, CLTX 6, CLTX 176).
Pattern development using flat pattern & draping methods.

Limits on Enrollment:

Schedule of Classes Information:
Description: Further studies in patternmaking techniques, with an emphasis on professional skills, unique styling details, and more complex design components. In addition to women's wear, patterns for jackets, coats, and active wear for men's and children's wear are discussed. Development of specialized slopers (such as jackets, etc.) included. (Grade or P/NP)

Prerequisites/Corequisites: Course Completion of FASH 62A (or CLTX 50A or CLTX 5A or CLTX 5 or CLTX 175)
Recommended: Previous or concurrent enrollment in FASH 60 (formerly CLTX 60, CLTX 6, CLTX 176). Pattern development using flat pattern & draping methods.
Limits on Enrollment:
Transfer Credit:
Repeatability: Two Repeats if Grade was D, F, NC, or NP

ARTICULATION, MAJOR, and CERTIFICATION INFORMATION:

AS Degree:	**Area**	Effective:	Inactive:
CSU GE:	**Transfer Area**	Effective:	Inactive:
IGETC:	**Transfer Area**	Effective:	Inactive:
CSU Transfer:	Effective:	Inactive:	
UC Transfer:	Effective:	Inactive:	

CID:

Certificate/Major Applicable:
Certificate Applicable Course

COURSE CONTENT

Outcomes and Objectives:
Upon completion of the course, students will be able to:
1. Create new, original designs using a variety of patternmaking and draping techniques.
2. Prepare accurate, workable patterns using industry standards.
3. Interpret complicated designs and assess the appropriate pattern development technique for that design.
4. Adapt patterns for a variety of fabrics, including knits.
5. Develop a series of standard slopers for pants, jackets, coats, and knits.
6. Discuss the role of computer technology in apparel design.
7. Based on subsequent repeats, students will be able to apply techniques to:
    a. increasingly complex applications
    b. increasingly complex patterns
    c. fabric manipulation with a variety of fabric textures
    d. increasingly complex fitting issues and adjustments
    e. gain confidence and speed

Topics and Scope:

I. Review of basic flat pattern techniques
II. Review of basic draping techniques
III. Review and discuss current trends in apparel design
IV. Patternmaking topics for women, men, and children
    A. Jackets and coats
    B. Complicated details in collars, pockets, cowls, sleeves, and other details pertinent to the student's designs.

C. Pants and jumpsuits
D. Active wear, including leotards and bathing suits
E. Working with varying degrees of stretch in fabric
V. Overview of computer applications in patternmaking and apparel design
VI. Professional standards
A. Develop production quality patterns from working sketches
B. Accurately mark and label patterns for production
C. Complete patterns quickly and efficiently
VII. Role of computer technology in apparel design
A. PAD (Patternmaking and Apparel Design) software
B. Gerber software
C. Electra software
VIII. Repeating students will practice speed and efficiency

Assignment:

1. Complete one specialty sloper (i.e., pants, leotard, basic knit, jacket).
2. Complete six half scale practice problems in utilizing both flat pattern and/or draping for unusual or complicated designs, utilizing industry standards.
3. Develop a series of 2-3 original designs and a completed garment from those designs utilizing advanced pattern development techniques.   (Patternmaking and draping processes given in class.)
4. Reading from text 5 to 15 pages per week.
5. Repeating students will be using more complex processes using advanced software and to improve speed and efficiency.

Methods of Evaluation/Basis of Grade:

Writing: Assessment tools that demonstrate writing skills and/or require students to select, organize and explain ideas in writing.

None, This is a degree applicable course but assessment tools based on writing are not included because problem solving assessments and skill demonstrations are more appropriate for this course.	Writing 0 - 0%

Problem Solving: Assessment tools, other than exams, that demonstrate competence in computational or non-computational problem solving skills.

Homework problems: 6 half scale practice problem designs	Problem solving 20 - 40%

Skill Demonstrations: All skill-based and physical demonstrations used for assessment purposes including skill performance exams.

Performance exams, specialty sloper, 6 half scale designs, 1 full scale sloper or foundation, 1 to 2 full scale pattern fashion garments, completed garment	Skill Demonstrations 40 - 60%

Exams: All forms of formal testing, other than skill performance exams.

Exams: short answers, multiple choice, true false	Exams 5 - 10%

Other: Includes any assessment tools that do not logically fit into the above categories.

Participation and attendance	Other Category 5 - 10%

Representative Textbooks and Materials:
Pattern-Making for Fashion Design, Armstrong, 4th edition, 2009